

L Number	Hits	Search Text	DB	Time stamp
48	1076	438/275,981.ccls.	USPAT; US-PGPUB	2004/09/09 16:42
49	79330	silicon adj nitride	USPAT; US-PGPUB	2004/09/09 16:42
50	5648	"Si.sub.3N.sub.4"	USPAT; US-PGPUB	2004/09/09 16:42
51	959	Si3N4	USPAT; US-PGPUB	2004/09/09 16:42
52	346	"Si.sub.xN.sub.y"	USPAT; US-PGPUB	2004/09/09 16:42
53	96	SixNy	USPAT; US-PGPUB	2004/09/09 16:43
54	60622	SiN	USPAT; US-PGPUB	2004/09/09 16:43
55	579	438/275,981.ccls. and ((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy or SiN)	USPAT; US-PGPUB	2004/09/09 17:07
56	167518	wafer\$1	USPAT; US-PGPUB	2004/09/09 17:07
57	665888	substrate\$1	USPAT; US-PGPUB	2004/09/09 17:07
58	6330	pre\$1clean\$3	USPAT; US-PGPUB	2004/09/09 17:08
59	2726	buffered adj hydrofluoric adj acid	USPAT; US-PGPUB	2004/09/09 17:09
60	1111	BHF	USPAT; US-PGPUB	2004/09/09 17:09
61	7582	ammonium adj fluoride	USPAT; US-PGPUB	2004/09/09 17:11
62	677	"NH.sub.4F"	USPAT; US-PGPUB	2004/09/09 17:13
63	16301	hydrogen adj fluoride	USPAT; US-PGPUB	2004/09/09 17:13
64	59869	HF	USPAT; US-PGPUB	2004/09/09 17:15
65	75005	de\$1ionized adj (water or "H.sub.2O")	USPAT; US-PGPUB	2004/09/09 17:14
66	1581	HF adj (gas or vapor\$1)	USPAT; US-PGPUB	2004/09/09 17:15
67	1	((wafer\$1 or substrate\$1) same pre\$1clean\$3 same ((buffered adj hydrofluoric adj acid) or BHF) same ((ammonium adj fluoride) or "NH.sub.4F"))	USPAT; US-PGPUB	2004/09/09 17:19
68	2	pre\$1clean\$3 same ((buffered adj hydrofluoric adj acid) or BHF) same ((ammonium adj fluoride) or "NH.sub.4F"))	USPAT; US-PGPUB	2004/09/09 17:20
69	21	((wafer\$1 or substrate\$1) same pre\$1clean\$3 same ((buffered adj hydrofluoric adj acid) or BHF)	USPAT; US-PGPUB	2004/09/09 17:27
70	742	diluted adj HF	USPAT; US-PGPUB	2004/09/09 17:27
71	925	((wafer\$1 or substrate\$1) near3 pre\$1clean\$3)	USPAT; US-PGPUB	2004/09/09 17:29
72	2284	((((wafer\$1 or substrate\$1) near3 pre\$1clean\$3)) same ((buffered adj hydrofluoric adj acid) or BHF) or (diluted adj HF) or (HF adj (gas or vapor\$1)))	USPAT; US-PGPUB	2004/09/09 17:30
73	6	((((wafer\$1 or substrate\$1) near3 pre\$1clean\$3)) same (((buffered adj hydrofluoric adj acid) or BHF) or (diluted adj HF) or (HF adj (gas or vapor\$1))))	USPAT; US-PGPUB	2004/09/09 17:33
74	33646	clean\$3 near4 (wafer\$1 or substrate\$1)	USPAT; US-PGPUB	2004/09/09 17:33

75	305	(clean\$3 near4 (wafer\$1 or substrate\$1)) same (((buffered adj hydrofluoric adj acid) or BHF) or (diluted adj HF) or (HF adj (gas or vapor\$1)))	USPAT; US-PGPUB	2004/09/09 17:40
76	4070	dilute\$1 adj (HF or (hydrofluoric adj acid))	USPAT; US-PGPUB	2004/09/09 17:42
77	244	(de\$1ionized adj (water or "H.sub.2O")) same (dilute\$1 adj (HF or (hydrofluoric adj acid)))	USPAT; US-PGPUB	2004/09/09 17:43
78	136406	silicon adj \$2oxide	USPAT; US-PGPUB	2004/09/09 17:44
79	134116	"SiO.sub.2"	USPAT; US-PGPUB	2004/09/09 17:44
80	6905	SiO2	USPAT; US-PGPUB	2004/09/09 17:44
81	28	((de\$1ionized adj (water or "H.sub.2O")) same (dilute\$1 adj (HF or (hydrofluoric adj acid)))) same ((silicon adj \$2oxide) or "SiO.sub.2" or SiO2)	USPAT; US-PGPUB	2004/09/09 18:03
82	279	(HF adj (gas or vapor\$1)) same ((silicon adj \$2oxide) or "SiO.sub.2" or SiO2)	USPAT; US-PGPUB	2004/09/09 18:03